

ABSTRACT

[Object] In a CMP conditioner in which abrasive grains are fixed to a protrusion protruded from an upper surface of a base, the abrasive grains are stably fixed to prevent a scratch from being generated due to detachment of the abrasive grains and a space for holding a polishing fluid is surely ensured between a protrusion section of the protrusion surrounding the abrasive grains and the pad upon dressing.

[Solving means] In the CMP conditioner in which protrusions 3 and 4 are protruded from an upper surface 2 of a base 1 which rotates around an axis line and a plurality of abrasive grains 5 is fixed to the protrusions 3 and 4, the abrasive grains 5 are fixed such that the abrasive grains are not protruded from a virtual extending surface P which extends from the peripheries 3C and 4C of a protrusion sections 3A and 4A, which faces a protrusion directions 3A and 4A of the protrusions 3 and 4, along the axis line.